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(54) CYCLOOLEFIN BASED ADDITION COPOLYMER, ITS COMPOSITION FOR
CROSSLINKAGE, ITS CROSSLINKED SUBSTANCE, OPTICALLY TRANSPARENT MATERIAL,
AND METHOD FOR MANUFACTURING CYCLOOLEFIN BASED ADDITION COPOLYMER

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a cycloolefin based addition copolymer that contains a reactive silyl group having a specific structure, has excellent optical transparency, heat resistance and adhesiveness, and can produce crosslinked substance having improved dimensional stability, solvent and chemicals resistance by crosslinking.

SOLUTION: The cycloolefin based addition copolymer containing the reactive silyl group that is made by addition polymerization between a cycloolefin compound having the reactive silyl group such as 5-[1',4',4'-trimethyl-2',6'-dioxo-1'-silacyclohexyl]-bicyclo[2.2.1]hepto-2-en and other cycloolefin compound such as bicyclo[2.2.1]hepto-2-en, a composition for crosslinkage made by combining with a specific crosslinking agent, the crosslinked substance made by crosslinking the composition, an optical material containing the copolymer, the composition or the crosslinked substance.

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